



Seeing beyond



ZEISS AWARD

for Talents in Photomask
Industry at EMLC 2026

Turn your research into recognition.

Submit your paper in the field of lithography and photomasks now and win participation in the ZEISS European Summer School along with a 2,500 EUR prize.

Take this opportunity to showcase your ideas and research, receive valuable feedback and connect with experts. The award will be presented at the European Mask and Lithography Conference (EMLC), which will take place from June 22-24, 2026, in Jena. Find more informations on www.emlc-conference.com.

The abstract submission deadline is **February 18, 2026**.

Assessment - Award Committee

The award will be assessed by an award committee consisting of members of the EMLC Program Committee. Contributions will be judged for technical merit, relevance of the topic to the industry and the author's ability to explain the work.

The Award - Invitation to ZEISS European Summer School & Donation

Winners will be awarded a ZEISS certificate and a trophy. He or she will be invited to the ZEISS European Summer School in Oberkochen, Germany, which will take place in July 22-23, 2026. There, students get deep insights into the ZEISS semiconductor optics manufacturing and related aspects of semiconductor technology. The winner will have the opportunity to present his/ her paper in this unique environment. Travel costs for the ZEISS European Summer school will be covered.

Donation

In addition, a donation to the amount of 2,500 EUR will be granted.

Requirements for Consideration

- The student must present a poster or presentation at European Mask and Lithography Conference
- The students must identify themselves as a student during abstract submission
- The student must be the lead manuscript author
- The student must attend the conference and present it during the session or be present during the poster session